

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Hada et al.
Appl. No.	:	10/557,694
Filed	:	November 22, 2005
For	:	RESIN FOR PHOTORESIST COMPOSITION, PHOTORESIST COMPOSITION AND METHOD FOR FORMING RESIST PATTERN
Examiner	:	Eoff, A.
Group Art Unit	:	1795

**AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION**

**Mail Stop AF**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed November 19, 2007, please amend the above-referenced application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.

DO NOT ENTER: /A.E./

03/04/2008